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Author and Subject Index
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The Computer-Derived 1991 Journal Index

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2. Given any topic, go to the subject index and search for the key word itself.
3. For a detailed explanation and meaning of symbols and abbreviations, see the sample pages before the individual author and title index and subject index.
4. Chemical formulae cannot be reproduced directly because the conventional computer printout appears in capital letters only. For example, Bi3 could be three atoms of bismuth or boron triiodide.

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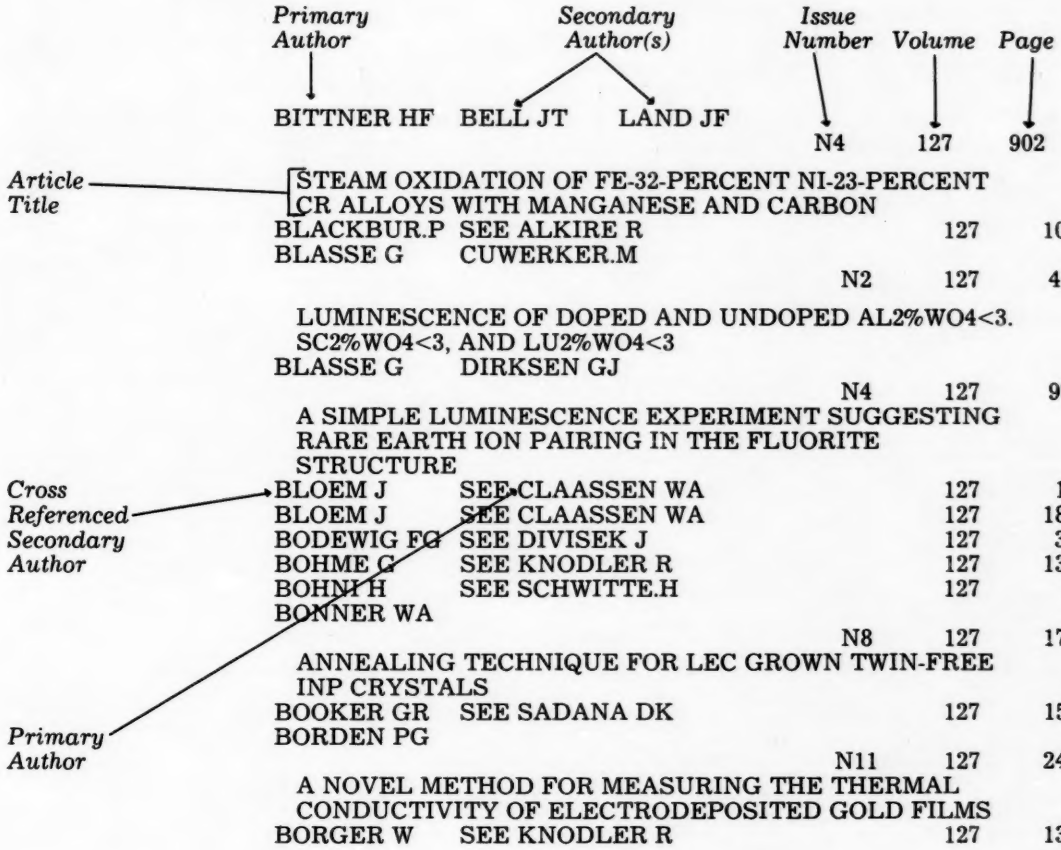
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